

FIG. 1

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Applicant: Kwan, et al.
Title: METHOD AND APPARATUS FOR
CLEANING A SEMICONDUCTOR WAFER
PROCESSING SYSTEM
Serial No. 09/494,327

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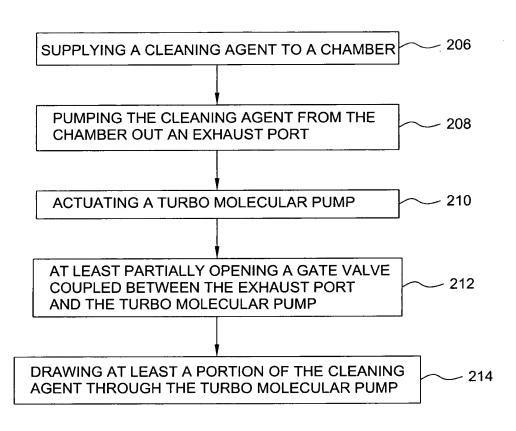


FIG. 2

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